# REQUEST **FOR** CONTINUED EXAMINATION (RCE) TRANSMITTALO PE

# MAIL STOP RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Application Number	10/084,204
Confirmation Number	6177
Filing Date	February 28, 2002
First Named Inventor	Takako SUZUKI
Group Art Unit	1752
Examiner Name	John S. Y. Chu
Matter Number	Q67844

Subsection (b) of 35 U.S.C. § 132, effective on May 29, 2000, provides for continued examination of an utility or plant application filed on or after June 8, 1995	POSITIVE PHOTORESIST COMPOSITION AND PROCESS FOR FORMING RESIST Title PATTERN USING SAME
This is a Request for Continued Examination (RCE) under 3'	
1. SUBMISSION REQUIRED UNDER 37 C.F.R. § 1.114  a. □ Previously submitted i. □ Please enter and consider the amendment(s)/repreviously filed on ii. □ Consider the arguments in the Appeal Brief or iii.□ Other  b. ☑ Enclosed i. ☑ Amendment/Reply ii. □ Affidavit(s)/Declaration(s) iii.☑ Information Disclosure Statements (IDS) iv. ☑ Petition for Extension of Time v. □ Other  2. MISCELLANEOUS	reply under 37 C.F.R. § 1.116 Reply Brief previously filed on  ication is requested under 37 C.F.R. § 1.103(c) for a
Checks for the RCE statutory fee of \$770.00 and for (1) month) of \$110.00 are attached. The USPTO is directed Issue Fee and the Publication Fee, to Deposit Account No. 19 Deposit Account. A duplicate copy of this transmittal letter is CORRESPONDE Direct all correspondence to the address for SUGHRUE MI	the Petition for Extension of Time statutory fee (for one and authorized to charge all required fees, except for the 9-4880. Please also credit any overpayments to said is attached.  ENCE ADDRESS  ON, PLLC filed under the Customer Number listed below:
/31/2004 HVUONG1 00000059 10084204 233	
FC:1801 770.00 OP CUSTOMER	
SIGNATURE O	F ATTORNEY
Name Patrick F. Gallagher	Registration No. 54,109
Signature Februl Cally	Date September 20, 2004

### PATENT APPLICATION

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q67844

Takako SUZUKI, et al.

Appln. No.: 10/084,204

Confirmation No.: 6177 Group Art Unit: 1752

Filed: February 28, 2002 Examiner: John S. Y. Chu

For: POSITIVE PHOTORESIST COMPOSITION AND PROCESS FOR FORMING RESIST

PATTERN USING SAME

## AMENDMENT UNDER 37 C.F.R. § 1.114(c)

#### MAIL STOP RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

A RCE and Petition for Extension of Time (for one (1) month) is filed concurrently herewith, thus extending the time for responding to the Final Office Action of May 18, 2004, from August 18, 2004, to September 20, 2004 (September 18, 2004 being a Saturday). Please amend the above-identified application as follows:

### TABLE OF CONTENTS

AMENDMENTS TO THE CLAIMS	.2
REMARKS	.5